

1 **Supporting Materials**

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5 **Microscopy Visualization of Carrier Transport in CdSeTe/CdTe**
6 **Solar Cells**

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44 Table S1. Cell performance of unstressed and stressed devices.

Cell	Unstressed				Stressed			
	V _{oc} (mV)	J _{sc} (mA/cm ²)	FF (%)	Eff. (%)	V _{oc} (mV)	J _{sc} (mA/cm ²)	FF (%)	Eff. (%)
1	829.2	27.6	72.6	16.6	787.5	28.5	45.9	10.3
2	828.6	27.2	74.4	16.8	786.6	28.3	47.9	10.7
3	829.2	27.8	75.0	17.3	784.5	27.7	56.8	12.4
4	829.9	27.7	72.4	16.6	789.9	28.8	43.1	9.8
5	829.3	27.4	74.8	17.0	790.3	27.6	46.9	10.2
6	828.4	27.2	75.4	17.0	790.7	26.9	51.8	11.0
7	829.5	28.4	70.3	16.5	792.0	28.6	35.2	8.0
8	829.4	28	73.9	17.1	792.6	29.4	42.4	9.9
9	827.9	27.2	75.2	16.9	792.9	28.5	50.2	11.3
10	829.2	28.4	72.8	17.1	795.9	28.8	45.3	10.4
11	830.4	28.2	74.3	17.4	794.8	29.7	47.4	11.2
12	829.1	27.9	75.7	17.5	792.6	29.1	51.5	11.9
13	750.4	29.1	66.4	14.5	717.9	29.0	51.0	10.6
14	752.1	29.9	64.1	14.4	723.9	29.4	46.3	9.9
15	763.4	32.0	66.9	16.4	728.4	29.8	38.1	8.3
16	756.2	30.3	67.6	15.5	719.0	30.7	41.9	9.2

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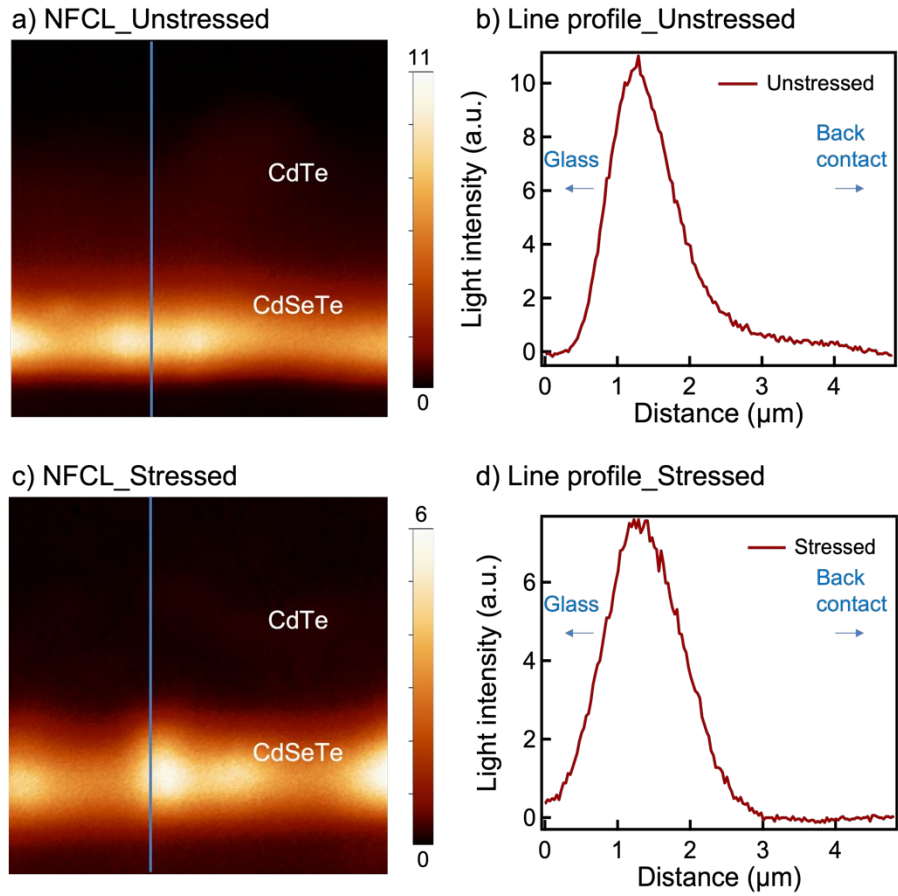
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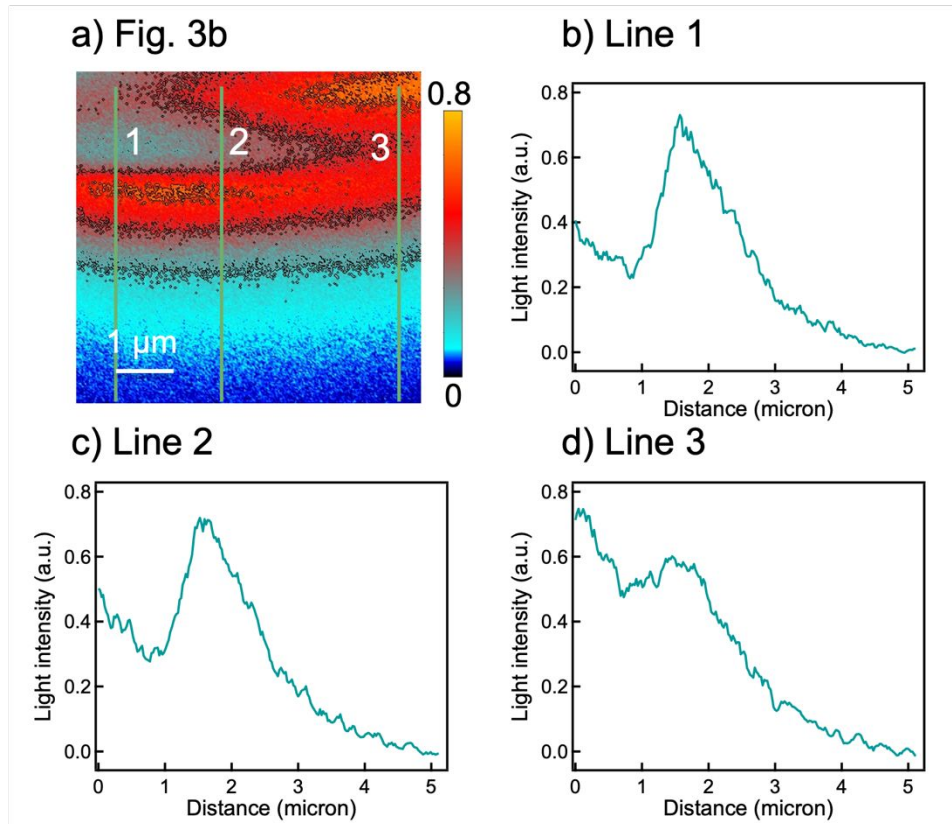
Table S2. Cell performance change and statistical results of unstressed and stressed devices.

Cell	Absolute change in performance				Change in performance relative to t=0 h			
	ΔV_{oc} (mV)	ΔJ_{sc} (mA/cm ²)	ΔFF (%)	$\Delta Eff.$ (%)	ΔV_{oc} (%)	ΔJ_{sc} (%)	ΔFF (%)	$\Delta Eff.$ (%)
1	-41.7	0.9	-26.7	-6.3	-5.0	3.3	-36.8	-38.0
2	-42.0	1.1	-26.5	-6.1	-5.1	4.0	-35.6	-36.3
3	-44.7	-0.1	-18.2	-4.9	-5.4	-0.4	-24.3	-28.3
4	-40.0	1.1	-29.3	-6.8	-4.8	4.0	-40.5	-41.0
5	-39.0	0.2	-27.9	-6.8	-4.7	0.7	-37.3	-40.0
6	-37.7	-0.3	-23.6	-6.0	-4.6	-1.1	-31.3	-35.3
7	-37.5	0.2	-35.1	-8.5	-4.5	0.7	-49.9	-51.5
8	-36.8	1.4	-31.5	-7.2	-4.4	5.0	-42.6	-42.1
9	-35.0	1.3	-25.0	-5.6	-4.2	4.8	-33.2	-33.1
10	-33.3	0.4	-27.5	-6.7	-4.0	1.4	-37.8	-39.2
11	-35.6	1.5	-26.9	-6.2	-4.3	5.3	-36.2	-35.6
12	-36.5	1.2	-24.2	-5.6	-4.4	4.3	-32.0	-32.0
13	-32.5	-0.1	-15.4	-3.9	-4.3	-0.3	-23.2	-26.9
14	-28.2	-0.5	-17.8	-4.5	-3.7	-1.7	-27.8	-31.3
15	-35.0	-2.2	-28.8	-8.1	-4.6	-6.9	-43.0	-49.4
16	-37.2	0.4	-25.7	-6.3	-4.9	1.3	-38.0	-40.6
Avg.	-37.0	0.4	-25.6	-6.2	-4.6	1.5	-35.6	-37.5
Std.	4.0	0.9	5.1	1.2	0.4	3.2	7.0	6.8

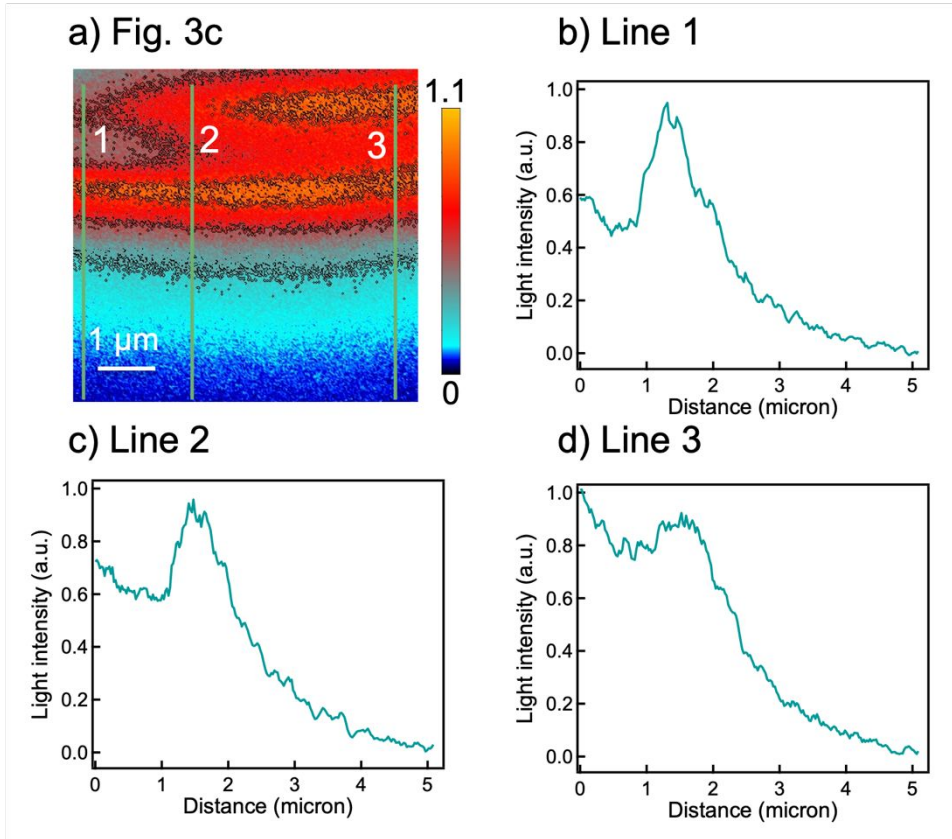
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49 Figure S1. Near-field cathodoluminescence results. a) unstressed CdSeTe/CdTe device; b) light intensity
 50 profile of NF-CL marked in a); c) stressed CdSeTe/CdTe device; d) light intensity profile of NF-CL
 51 marked in c).
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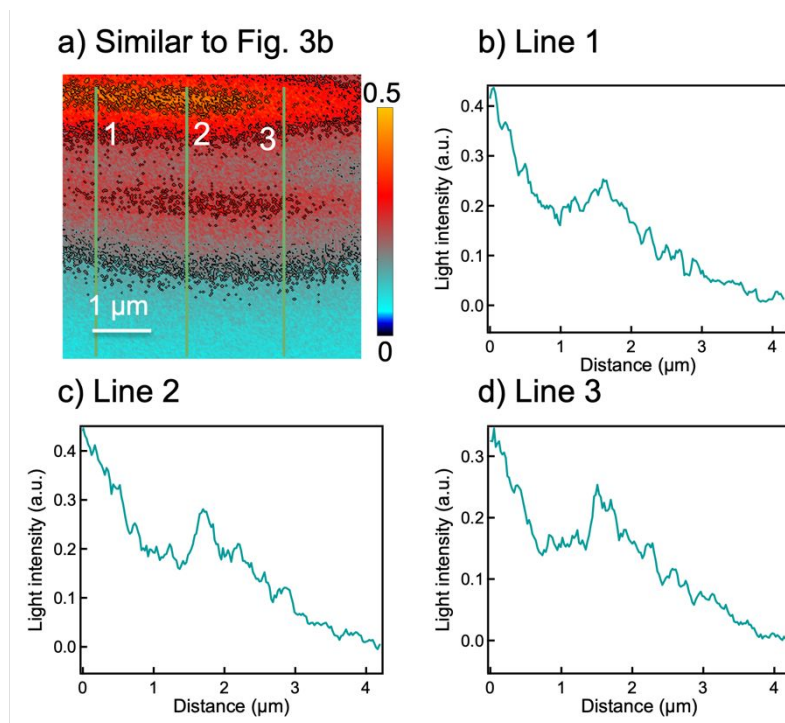
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 56 Figure S2. More decay line profiles in Figure 3b, showing the carrier transport decay profiles are not a
 57 single decay.
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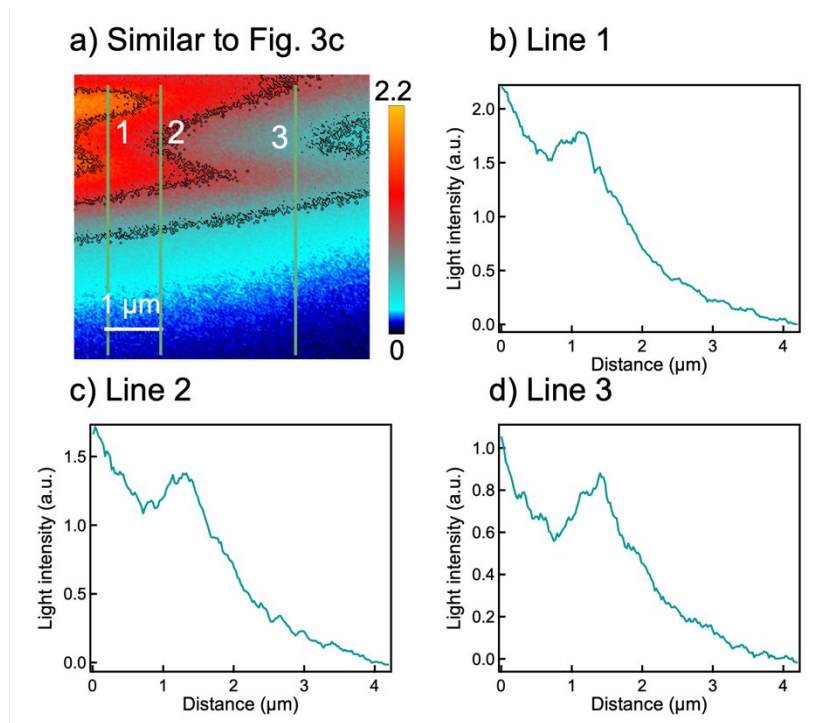
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Figure S3. More decay line profiles in Figure 3c, showing the carrier transport decay profiles are not a single decay.

82 On another unstressed device, we show the dual peak feature is reproducible:
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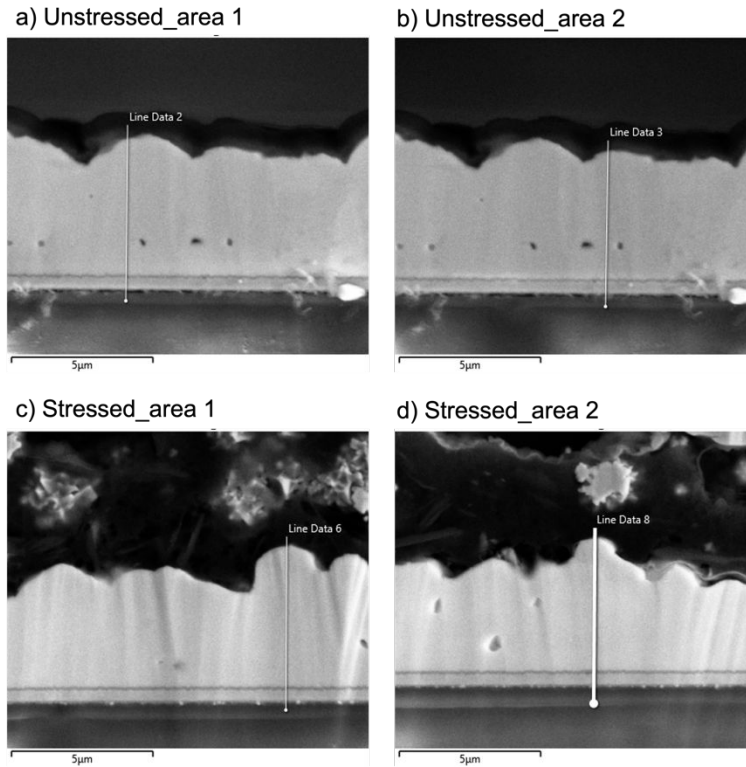


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85 Figure S4. Transport Imaging results on another unstressed device, experimental set up similar to Figure
86 3b. a) TI mapping; b-d) light intensity profiles of TI marked in a), showing the carrier transport decay
87 profiles are not a single decay.
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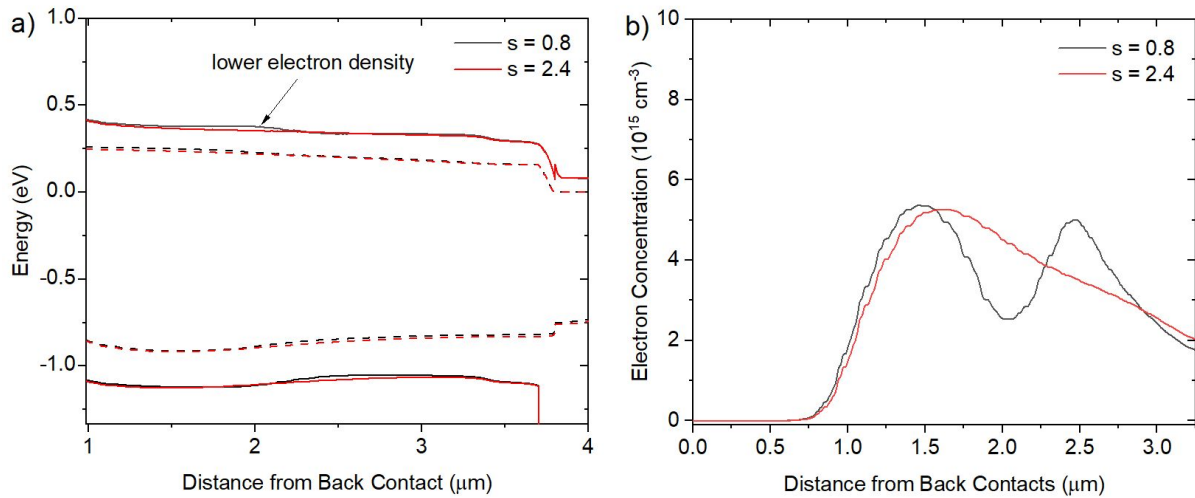
Figure S5. Transport Imaging results on another unstressed device, experimental set up similar to Figure 3c. a) TI mapping; b-d) light intensity profiles of TI marked in a), showing the carrier transport decay profiles are not a single decay.



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Figure S6. SEM EDS on multiple locations of unstressed and stressed cells, line profiles shown in Figure 5. Note that we chose areas with similar thickness for better comparison. In Figure 5, the shoulder at 3 µm may be due to rough topography, because EDS has a large signal generation volume, the signal at ~3 µm may involve signal from different amounts of underneath materials.

135 Figure S7 (a) shows the band edges for the two smoothing parameters $s = 0.8$ and $s = 2.4$. The
 136 e-beam is located at $d = 1.4 \mu\text{m}$ with a generation rate that is sufficient to screen the built-in field
 137 near the junction and cause slight fluctuations in the band edges. A zoomed in region of the band
 138 edges near the observed TI peaks is shown to illustrate the subtle changes in the energetic
 139 differences between the quasi-Fermi levels and their respective bands for the two smoothing
 140 parameters. The fluctuations are less pronounced for the $s = 2.4$ case. Electron density profiles
 141 corresponding to the band edges are shown in Figure S7(b), exhibiting the two peaks for the $s =$
 142 0.8 case that correspond to the peaks in radiative recombination and the observed TI profiles. There
 143 is only a single electron density peak for the $s = 2.4$ case. The hole density profiles follow the
 144 same pattern in this region (not shown).



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 147 Figure S7. (a) band edges and (b) electron density profiles for e-beam excitation at $d = 1.4 \mu\text{m}$ with band
 148 gap smoothing parameters of $s = 0.8$ and $s = 2.4$. A close-up of the excitation region shows that at $s =$
 149 0.8 , slight fluctuations in the band edges (a) can cause double or single peaks in the electron density (b). A
 150 similar result holds for hole density, resulting in the observed peaks in radiative recombination and,
 151 therefore, TI measurements.

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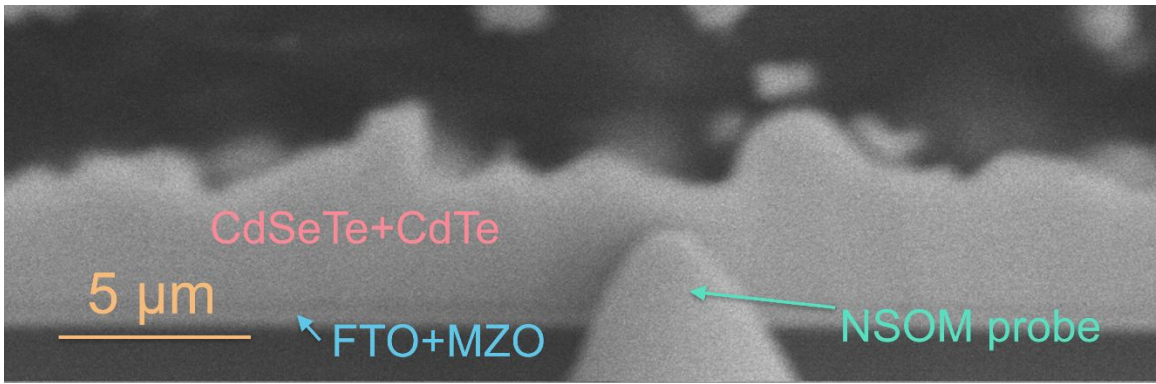
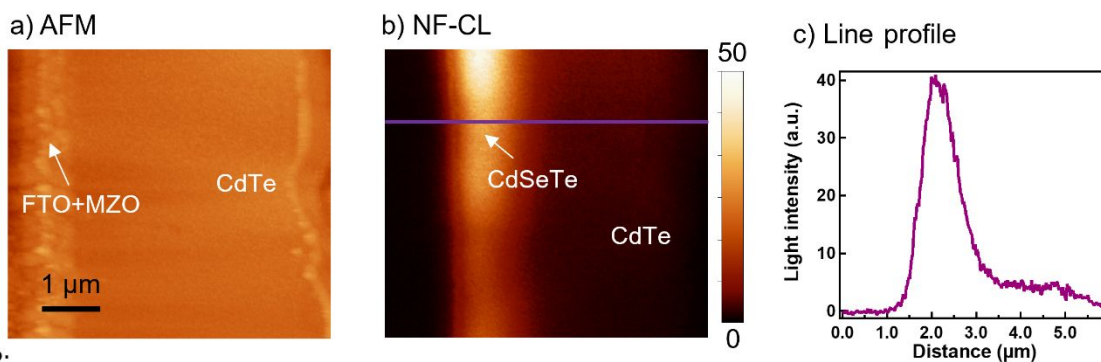


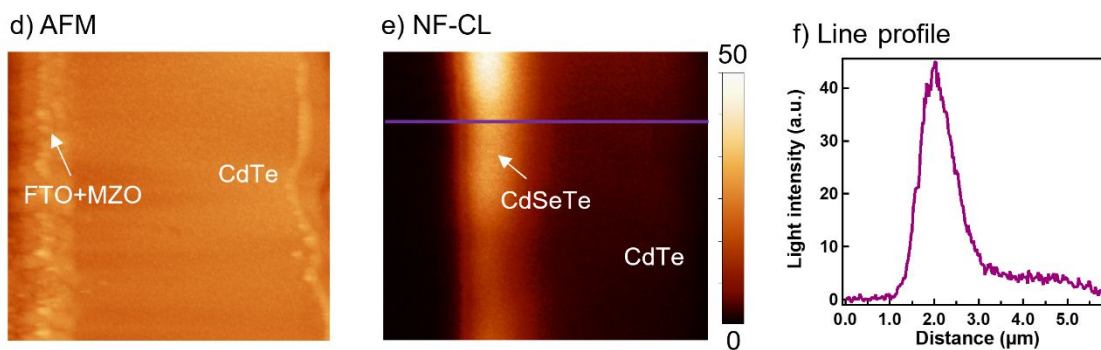
Figure S8. NSOM probe landing on the cross-sectional surface of a CdSeTe/CdTe cell.

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Scan 1:



Scan 2:



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177 Figure S9. Two consecutive scans of NF-CL on the same location of unstressed CdSeTe/CdTe devices.
178 The electron beam condition is 20 kV, 0.38 nA, which led to a different light intensity than Figure 2. The
179 results demonstrate reliable measurements with no carbon deposition contamination affects the NF-CL
180 and further TI analysis. The AFM data is shown to help visualize where the NF-CL data is coming from.

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195 Table S3. Baseline device model parameters¹⁻⁴.

Parameter	Symbol	Unit	SnO ₂ :F	Mg(Zn,O)	p-Cd(Se,Te)	n-Cd(Se,Te)
Thickness	h	nm	400	100	3,400	300
Band Gap	E_g	eV	3.6	3.75	1.5–1.39 ^(a)	1.39
Rel. Permittivity	ϵ		9.0	9.0	9.4	9.4
Electron Affinity	χ	eV	4.4	4.49 ^(b)	graded ^(a)	4.49
Mobility	μ_n, μ_p	cm ² /Vs	100, 25	1, 25	320, 40	320, 40
Lifetime	τ_n, τ_p	ns	0.1, 0.1	0.1, 0.1	2, 2	2, 2
Doping	N_A, N_D	cm ⁻³	n: 10 ¹⁷	n: 10 ¹⁴	p: 4x10 ¹⁴	n: 4x10 ¹⁵

196 Notes:

197 (a) Cd(Se,Te) bandgap was graded as described in main text. The affinity was graded such that
198 the band gap changes were completely accommodated by changes in the conduction band.199 (b) MZO electron affinity was reduced to 4.22 eV in the stressed device to account in part for
200 the observed FF loss.

- 201 • For the Schottky contacts, front and back metal work functions were set to 4.5 and 5.6 eV
202 (pre-stress)/5.5 eV (post-stress), respectively.
- 203 • Surface recombination velocities at the front and back contacts were set to 10⁷ cm/s.
- 204 • Cd(Se,Te)/MZO interface defect density was 10⁹ cm⁻² acceptor type with capture cross-
205 sections of 10⁻¹⁴ cm² located at mid-gap.
- 206 • Fitting the JV data required adding a series resistance of $R_s = 2 \Omega \text{ cm}^2$.

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208 **References**

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